Technologies
for microsystems
Process units
Wafer holder systems

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silicet
ETCHING TECHNOLOGY FOR MICROSYSTEMS

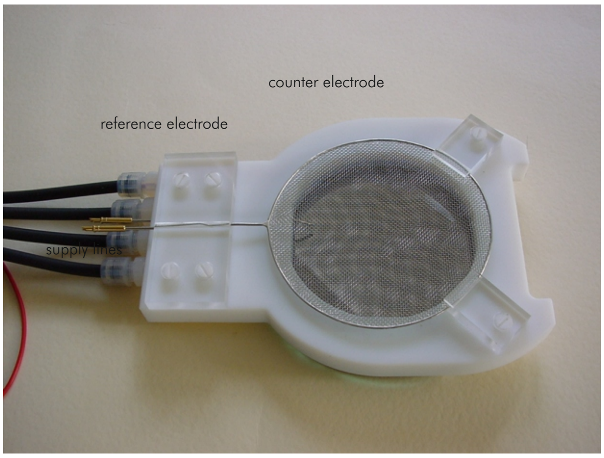
patented

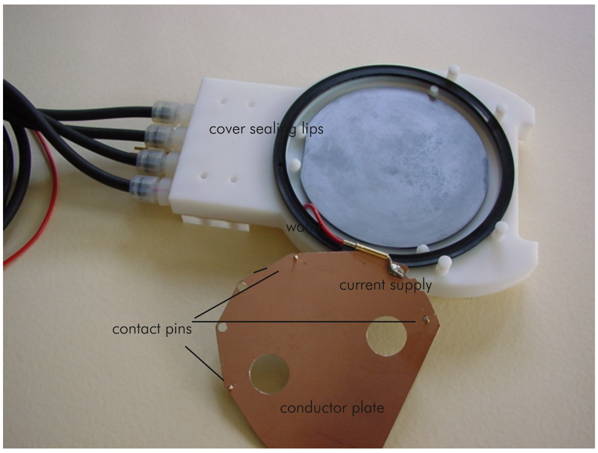
VACUUM-HOLDER **PLUS E**

Our patented Wafer Holder PLUS E with easy exchangeable sealing lips, is a new generation of holding device. Created for electro-chemical etching of silicon wafers.
The wafers are held securely by means of a vacuum, thus also protecting them reliably from the etching agent. The Wafer Holder PLUS E is equipped with an additional seal, which protects the entire wafer front including the edge from the etching agent.
The protected area behind the wafer is ventilated to provide pressure compensation.
Contacts within protected room. Regarding positioning please refer to downloads pin positioning.

Also available with doublesided contact.

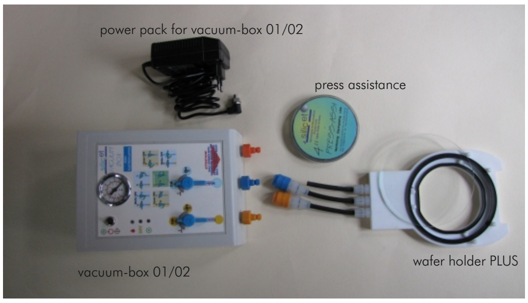
Equipment:	**Sealing Lips:**	**EPDM/FPM peroxide cured and sulfure-free**
	Supply lines:	**4 Norprene or Viton connecting tubes/**





reference electrode:
Pt/Ir 90/10%
d=1,50 mm, length 110 mm
(for wafer sizes up to 8")

counter electrode:
Pt/Ir 90/10%
no of meshs 100/cm², wire d= 0,25 mm
net d= 100 mm
(for wafer sizes 4 - 6")



subject to technical modifications - aug. 2010

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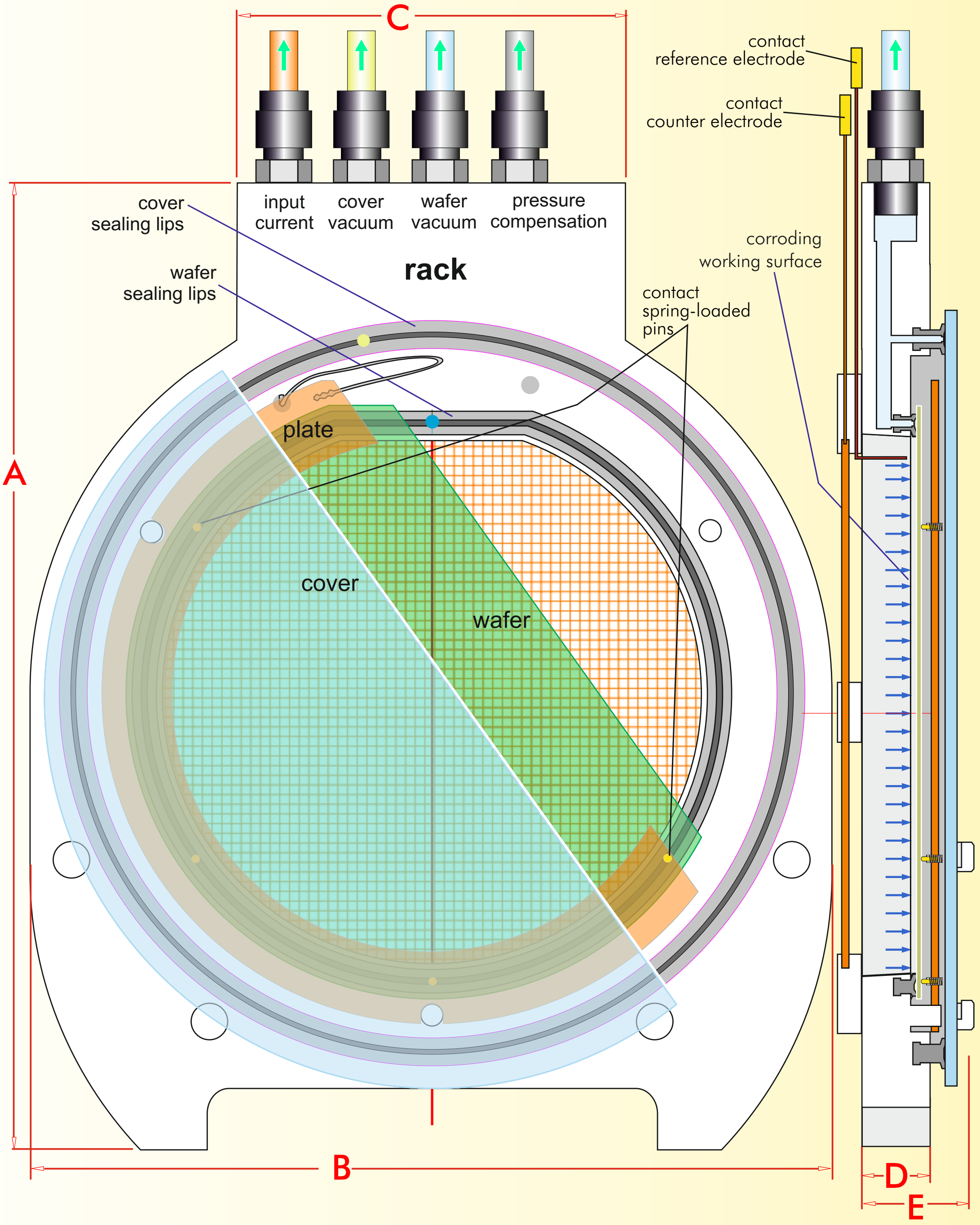
VACUUM-HOLDER **PLUS E**



Dimension	**2"**	**3"**	**4"**	**5"**	**6"**	**8"**
A - length	122 mm	145 mm	186 mm	239 mm	239 mm	313 mm
B - total width	80 mm	105 mm	132 mm	190 mm	190 mm	263 mm
C - width neck	80 mm	80 mm	80 mm	80 mm	84 mm	100 mm
D - thickness	12 mm	14 mm	14 mm	15 mm	15 mm	15 mm
E - compl. thickness	21 mm	22 mm	22 mm	22 mm	22 mm	24 mm
F - edge exclusion	5 mm	5 mm	5 mm	5 mm	5 mm	5 mm

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Etching technology
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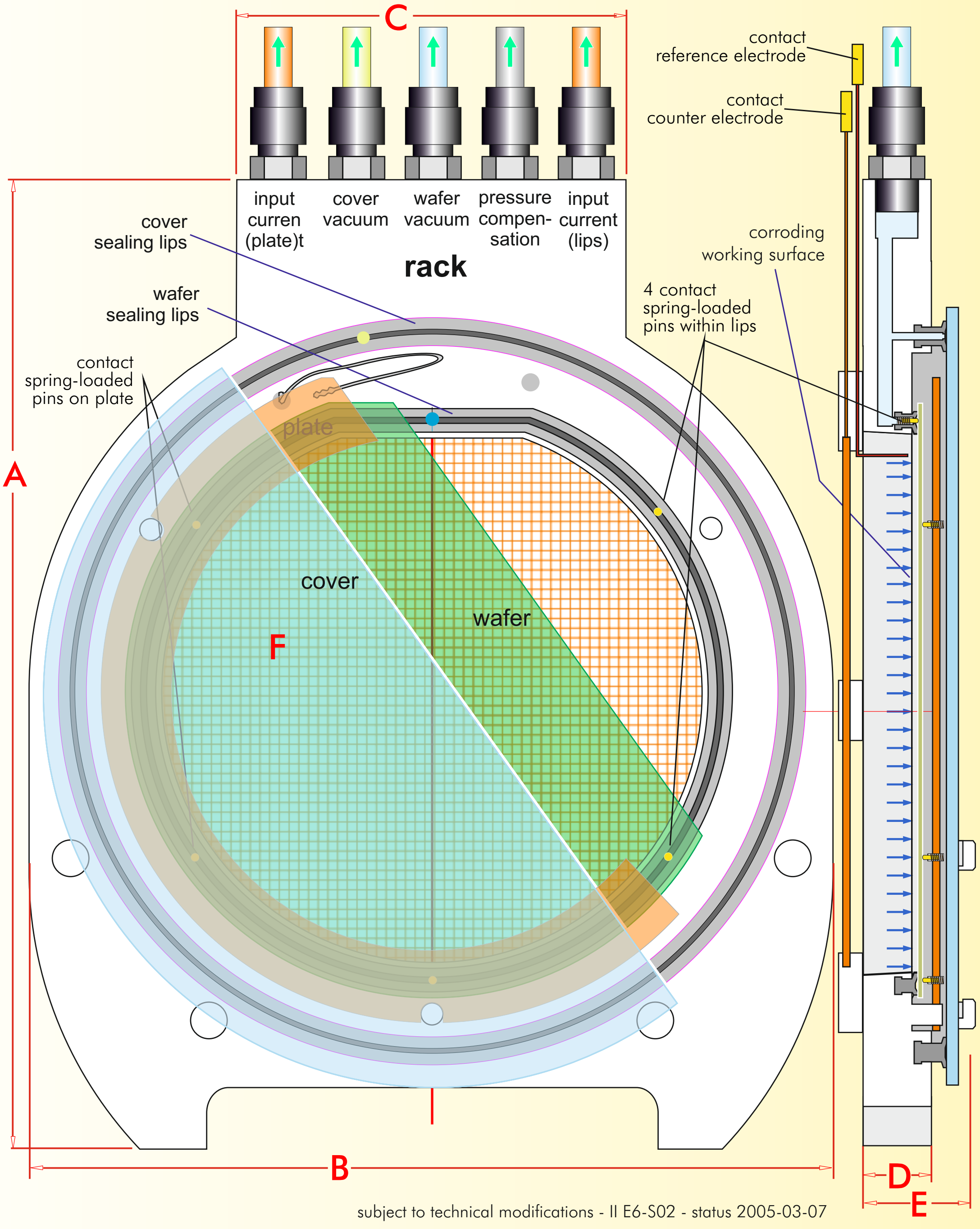
VACUUM-HOLDER

PLUS E contact from both sides



subject to technical modifications - II E6-S02 - status 2005-03-07

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